

AMENDMENTS TO THE CLAIMS

1. (Cancelled)

2. (Cancelled)

3. (Cancelled)

4. (Cancelled)

5. (Cancelled)

6. (Cancelled)

7. (Cancelled)

8. (Cancelled)

9. (Cancelled)

10. (Cancelled)

11. (Cancelled)

12. (Cancelled)

13. (Cancelled)

14. (Cancelled)
15. (Cancelled)
16. (Cancelled)
17. (Cancelled)
18. (Cancelled)
19. (Cancelled)
20. (Currently amended) A process for coating of substrates comprising:
- inserting a substrate into a process chamber;
 - dehydrating said substrate;
 - supplying a first ~~chemical~~ liquid silane to a heated vaporization chamber;
 - vaporizing said first ~~chemical~~ liquid silane; and
 - supplying the vapor of said first ~~chemical~~ liquid silane to a said process chamber, thereby
coating said substrate whereby said vapor of said first liquid silane reacts with the substrate to create a
layer, after dehydrating said substrate.
21. (Currently amended) The process of claim 20 further wherein said supplying a first ~~chemical~~ liquid silane comprises withdrawing said first ~~chemical~~ liquid silane from a first ~~chemical~~ liquid silane reservoir.

22. (Currently amended) The process of claim 21 wherein said withdrawing said first ~~chemical liquid~~ silane comprises withdrawing a specific volume of said first ~~chemical liquid~~ silane from said first ~~chemical liquid~~ silane reservoir.
23. (Currently amended) The process of claim 21, wherein said first ~~chemical liquid~~ silane reservoir is a chemical manufacturer's source bottle.
24. (Cancelled)
25. (Currently amended) The process of claim 20, wherein said dehydrating a substrate comprises:
inserting said substrate into said process chamber;
evacuating said chamber to a first pressure;
inputting a first gas into said process chamber after evacuating said chamber to a first pressure.
26. (Original) The process of claim 25 wherein said first gas is an inert gas.
27. (Original) The process of claim 26 wherein said inert gas is nitrogen.
28. (Original) The process of claim 25 wherein said first gas is heated.
29. (Original) The process of claim 25 further comprising re-evacuating said process chamber subsequent to said inputting a first gas into said process chamber.
30. (Original) The process of claim 29 wherein said re-evacuating said process chamber evacuates said process chamber to a second pressure.

31. (Original) The process of claim 30 wherein said second pressure is lower than said first pressure.
32. (Original) The process of claim 20 further comprising:
- supplying a second chemical to a heated vaporization chamber;
 - vaporizing said second chemical; and
 - supplying the vapor of said second chemical to said process chamber.
33. (Original) The process of claim 20 wherein said vaporizing said first ~~chemical~~ liquid silane occurs in a first vaporization chamber.
34. (Currently amended) The process of claim 33 wherein said vaporizing said first ~~chemical~~ liquid silane comprises heating said first ~~chemical~~ liquid silane.
35. (Currently amended) The process of claim 33 wherein said vaporizing said first ~~chemical~~ liquid silane comprises exposing said first ~~chemical~~ liquid silane to reduced pressure.
36. (Currently amended) The process of claim 34 wherein said vaporizing said first ~~chemical~~ liquid silane further comprises exposing said first ~~chemical~~ liquid silane to reduced pressure.
37. (Currently amended) The process of claim 32 wherein said vaporizing said first ~~chemical~~ liquid silane occurs in a first vaporization chamber.
38. (Original) The process of claim 37 wherein said vaporizing said second chemical occurs in said first vaporization chamber.
39. (Currently amended) The process of claim 38 wherein said vaporizing said first ~~chemical~~ liquid silane and said vaporizing said second chemical occur relatively simultaneously.

40. (Currently amended) A process for the coating of a substrate comprising:

inserting a substrate into a process chamber;

dehydrating said substrate;

delivering a first amount of a first ~~chemical~~ liquid silane to a vaporization chamber;

vaporizing said first ~~chemical~~ liquid silane; and

delivering the vaporized first ~~chemical~~ liquid silane into said process chamber, ~~thereby coating~~
~~said substrate whereby said vapor of said first liquid silane reacts with the substrate to create a layer,~~
after dehydrating said substrate.

41. (Original) The process of claim 40, wherein said substrate comprises glass.

42. (Cancelled)

43. (Currently amended) The process of claim 42 wherein said first liquid silane is an amino silane.

44. (Currently amended) The process of claim 42 wherein said first liquid silane is an epoxy silane.

45. (Currently amended) The process of claim 42 wherein said first liquid silane is a mercapto silane.

46. (Currently amended) The process of claim 40 wherein said delivering a first amount of a first
~~chemical~~ liquid silane to a vaporization chamber comprises:

withdrawing a first amount of a first ~~chemical~~ liquid silane from a first ~~chemical~~ liquid silane
reservoir; and

delivering said first amount of a first ~~chemical~~ liquid silane to said vaporization chamber.

47. (Currently amended) The process of claim 46 wherein said ~~chemical~~ first liquid silane reservoir is a chemical source bottle.

48. (Currently amended) The process of claim 46 further comprising replacing the lost volume of chemical in the first liquid silane reservoir with an inert gas.

49. (Original) The process of claim 48 wherein said inert gas is nitrogen.

50. (Currently amended) The process of claim 46 wherein said withdrawing a first amount of a first ~~chemical~~ liquid silane comprises withdrawing said first amount using a syringe pump.